RETICLE POD

Abstract

A container that provides support structure and environmental control means including, for example, minimal contact with a wafer or reticle contained therein that cooperates with wafer or reticle to provide a diffusion barrier mitigates against particles settling on a face of the wafer or reticle. The container includes a base having a flat, polished surface with protrusions upon which the wafer or reticle rests. The protrusions are of a geometry, such as a sphere, that imparts minimum contact with the wafer or reticle and suspends the wafer or reticle over the base, providing a gap thereberween. The gap isolates the wafer or reticle from the flat, polished surface of the base, but is dimensioned to inhibit migration of particles into the gap, thereby preventing contamination of sensitive surfaces of the wafer or reticle. Diffusion filters provide pressure equalization without filter media. Moveable reticle pins on the top cover provide reticle restraint. Dual containment pod embodiment provides further isolation and protection.

Fig. 1